

ABSTRACT OF THE DISCLOSURE
EXPOSURE APPARATUS, METHOD THEREOF, AND METHOD OF
MANUFACTURING ARTICLE

An exposure apparatus that exposes a substrate is provided. The apparatus comprises a stage configured to hold and move the substrate, and a controller configured to control focus driving of the stage based on a measurement value and a correction value obtained for the focus driving of the stage for a shot region on the substrate. The controller is configured to determine the correction value in accordance with an angle of view at a time of exposure.

(Fig. 1)